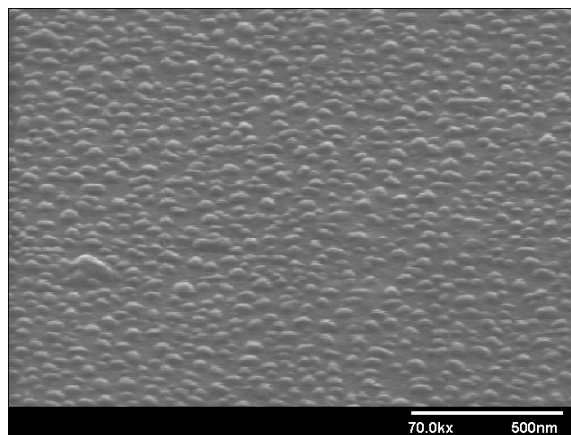
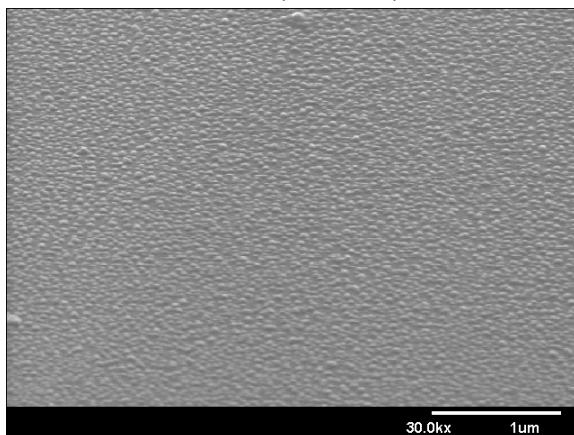
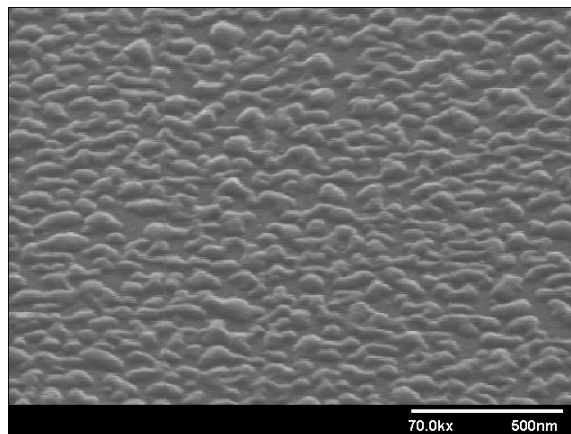
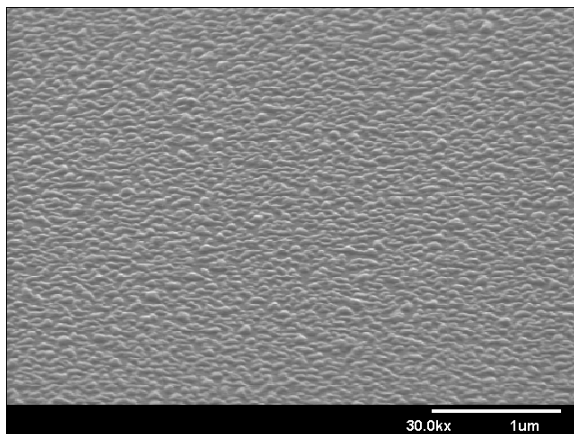


B3、550°C H₂:200 (Ni 7 nm)



B4、550°C H₂:200 (Ni 7 / TiN 20 nm)



B5、550°C H₂:200 (Ni 7 / TaN 10 nm)

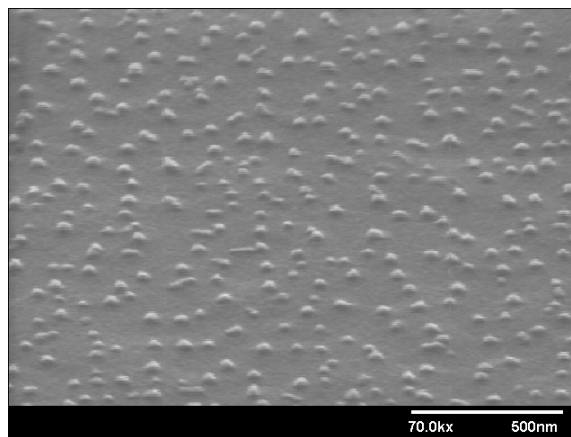
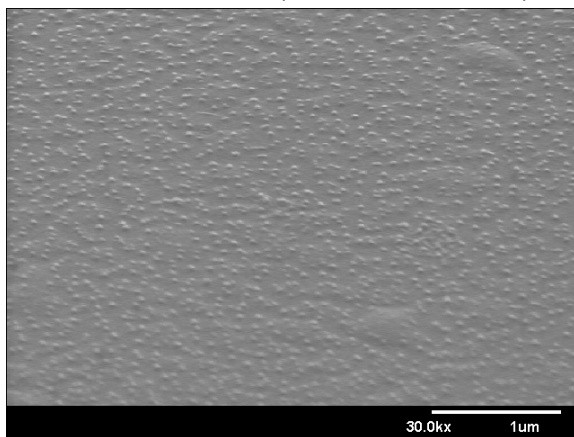


圖 4-18 製程 B 有緩衝層對照組試件(4、5) SEM 圖面(30、70 kx)